

STN 8 USPAT

(FILE 'HOME' ENTERED AT 14:00:51 ON 27 SEP 2002)

FILE 'USPATFULL' ENTERED AT 14:01:47 ON 27 SEP 2002

L1 229320 S SILICA OR SI2O3 OR SI(W)SUB(W)2(W)O(W)SUB(W)3
L2 647 S SI(3W)2(W)O(3W)3
L3 229658 S L1 OR L2
L4 67325 S AGGREGATE?
L5 457203 S PARTICLE?
L6 622019 S PRIMARY
L7 2477943 S DIA? OR SIZE#
L8 215584 S NM OR NMS OR NM. OR NMS. OR NANOMETER?
L9 221 S L3(P)L4(P)L5(P)L6(P)L7
L10 96 S L9(P)L8
L11 11 S L10(P)(OH OR HYDROX?)
L12 569370 S MICRON# OR MU OR MUS OR MU. OR MUS.
L13 94 S L9(P)L12
L14 3 S L13(P)(OH OR HYDROX?)
L15 36290 S (SILICA OR SI2O3 OR SI(3W)2(W)O(3W)3)/CLM
L16 21 S (SI(W)SUB(W)2(W)O(W)SUB(W)3)/CLM
L17 12897 S AGGREGAT?/CLM
L18 125880 S PARTICL?/CLM
L19 83021 S PRIMARY/CLM
L20 635892 S (DIA? OR SIZ?)/CLM
L21 32275 S (NM OR NMS OR NMS. OR NM. OR NANOMETER# OR NANO
METER#)/CLM
L22 107686 S (MICRON# OR MU OR MUS OR MU. OR MUS.)/CLM
L23 178456 S (OH OR HYDROX?)/CLM
L24 5 S (L15 OR L16) AND L17 AND L18 AND L19 AND L20 AND L21 AND L22
L25 5 S L24 NOT (L11 OR L14)
L26 1336 S (L15 OR L16)(10A)L23
L27 4123 S (L15 OR L16)(10A)L20
L28 121 S L26 AND L27 AND (L21 OR L22)
L29 106 S L28 AND (L17 OR L18 OR L19)
L30 35360 S (L1 OR L2)(10A)L7
L31 17853 S (L1 OR L2)(10A)(OH OR HYDROX?)
L32 1317 S L30(P)L31
L33 33 S L32(P)L8(P)L12
L34 27 S L33(P)(L4 OR L5 OR L6)
L35 33 S L33 OR L34
L36 33 S L35 NOT (L11 OR L14)
L37 55 S L32 AND PRECIP?/CLM
L38 71285 S (CMP OR POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR
PLANARIZ? O
L39 3 S L36 AND L38
L40 55 S L37 NOT L39

SET HIGH OFF
L41 30 S L40 AND (CMP OR POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR
PLAN
L42 30 S L41 NOT L39
SET HIGH ON
L43 30 S L40 AND L42
L44 14 S L43 AND (SIZE# OR DIA# OR DIA. OR DIAMETER?)/CLM

FILE 'USPATFULL' ENTERED AT 14:58:30 ON 27 SEP 2002

L45 4 S US4508607/PN OR US5064874/PN OR US5912098/PN OR US4680204/PN
L46 19203 S (OH OR HYDROX?)(P)(NM OR NMS OR NM. OR NMS. OR
NANOMETER? OR
L47 2 S (OH OR HYDROX?)(P)(NM2)
L48 3 S L45 AND (L46 OR L47)
L49 1 S L45 NOT L48
L50 365 S L7(P)L8(P)L3(P)(OH OR HYDROXY)
L51 41 S L50(P)PRECIP?
L52 0 S L51(P)NM2
SET HIGH OFF
L53 6 S L51 AND (POLISH? OR CHEMIPOLISH? OR CHEMIMECH? OR
PLANARIZ? O
L54 7 S L51 AND (SEMICONDUCT? OR WAFER? OR CHIP#)
L55 11 S L53 OR L54
SET HIGH ON
L56 11 S L51 AND L55
L57 30 S L51 NOT L56